TECHNICAL SPECIFICATIONS



HITACHI Inspire the Next



Optical system

- Multi-CMOS optics in Paschen-Runge mounting and optimised pixel resolution
- Focal length: 400 mm
- Wave length: 120 780 nm
- Peak position alignment

Typical applications

- Quality control for process and melt verification: analysis mode / grade identification
- All relevant alloying, residual, treatment, trace and tramp elements with low limits of detection
- · Fe: Alloys, cast iron alloys incl. N down to 10 ppm
- Al: Alloys, cast alloys, wrought alloys,...
- Cu: Bronze, Brass, Cu-Ni, ...
- · Ni: hasteloy ~inconel ~ monel, incl. N down to 20 ppm
- Ti: Ti pure, Ti.6-4 \sim Ti.8-Mn, including the possibility to determin gases such as H,O and N
- · Mg, Co, Pb, Sn, Zn alloys, solders and more

Readout system

 External PC-Workstation incorporating up-to-date technology with Microsoft[®] Windows[®] user interface

Solid state source

- Computer controlled parameters
- Frequency: 80 1000 Hz
- Voltage: 250 500 V
- · High energy pre spark (HEPS)



Argon supply

- Argon quality: min 4.8 (=99.998 % Ar)
- Argon quality: 5.0, if analysis of gases is required
- Input pressure: 3 bar

Environmental data

- Temperature range
 - Storage: -10° to +60°C
- In operation: 0° to +40°C
- Humidity range: 10 90 % (non-condensing)



Visit www.hitachi-hightech.com/hha for more information.



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